

APPARATUS AND METHOD FOR COATING A SUBSTRATE

Abstract

5 The present disclosure generally relates to an apparatus and a method for coating a substrate with a precursor material. The apparatus comprises: a support assembly for arranging the substrate such that a coating surface of the substrate faces substantially downwards; an inlet region for atomizing the precursor material in liquid form; a chamber fluidically connected to the inlet region for receiving the atomized precursor
10 material discharged from the inlet region, the chamber comprising a set of fluidic devices for breaking up the atomized precursor material; and an outlet region fluidically connected to the chamber for receiving the atomized precursor material communicated from the chamber, wherein the outlet region is configured for discharging the atomized precursor material substantially upwards to the substrate,
15 thereby coating the substrate coating surface with the precursor material.

Figure 1A